

Title (en)
MIRROR DEVICE FOR AN INTERFEROMETER DEVICE, INTERFEROMETER DEVICE AND METHOD FOR PRODUCING A MIRROR DEVICE

Title (de)
SPIEGELEINRICHTUNG FÜR EINE INTERFEROMETEREINRICHTUNG, INTERFEROMETEREINRICHTUNG UND VERFAHREN ZUM HERSTELLEN EINER SPIEGELEINRICHTUNG

Title (fr)
DISPOSITIF MIROIR POUR DISPOSITIF INTERFÉROMÉTRIQUE, DISPOSITIF INTERFÉROMÉTRIQUE ET PROCÉDÉ POUR RÉALISER UN DISPOSITIF MIROIR

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Application
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Abstract (en)
[origin: WO202229180A1] The invention relates to a mirror device (1) for an interferometer device (1), comprising: a first mirror layer (2) and a second mirror layer (3), which are arranged in parallel on top of one another and spaced apart from one another by a mirror layer spacing (d23), wherein the mirror layer spacing (d23) forms an intermediate space (5) between the first and the second mirror layer (2, 3), and wherein the intermediate space (5) includes a gas or a vacuum; and at least one spacing structure (4) which extends at least partially between the first and the second mirror layer (2, 3), and wherein the spacing structure (4) has a material that is the same as or different from the first and/or second mirror layer (2, 3).

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